Accepted Manuscript

Influences of semiconductor oxide fillers on the corrosion behavior of metals under coatings

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PII: S0013-4686(18)31865-6

DOI: 10.1016/j.electacta.2018.08.116

Reference: EA 32667

To appear in: Electrochimica Acta

Received Date: 28 May 2018

Accepted Date: 17 August 2018

Please cite this article as: Sijia Li, Wen Sun, Zhengqing Yang, Xinyu Zhang, Lida Wang, Guichang Liu, Influences of semiconductor oxide fillers on the corrosion behavior of metals under coatings, *Electrochimica Acta* (2018), doi: 10.1016/j.electacta.2018.08.116

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Influences of semiconductor oxide fillers on the corrosion 1 behavior of metals under coatings 2 3 Sijia Li, Wen Sun, Zhengqing Yang, Xinyu Zhang, Lida Wang, Guichang Liu* 4 Department of Materials Science and Chemical Engineering, Dalian University of 5 Technology, No.2 Linggong Road, Dalian 116024, China 6 *Corresponding author. Tel: 86-13322256529, Fax: 86-411-84986047. 7 E-mail address: gchliu@dlut.edu.cn 8 9 10 Abstract: Semiconductor oxides are widely used as coating fillers, while few studies have focused on the interactions between semiconductor fillers and metal substrates. In 11 this paper, common semiconductor fillers including TiO₂, Fe₂O₃ and Cu₂O were 12 prepared and incorporated into polyvinyl butyral coatings. Localized EIS, EIS, SEM 13 and electrochemical noise analysis were applied to study the corrosion behavior of 14 semiconductor/metal contacts at coating defects. Results revealed that TiO₂ and Fe₂O₃ 15 accelerated the corrosion of metals, while Cu₂O showed no promising effect. 16

Meanwhile, a micro-galvanic corrosion mechanism based on work function difference
and oxygen reduction reaction activity was proposed to explain the corrosionpromotion phenomenon.

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22 Keywords: Organic coatings; Semiconductor oxide; Localized EIS; Work function

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